

EUROPEAN MICROWAVE WEEK 2019

SIX DAYS THREE CONFERENCES ONE EXHIBITION

PORTE DE VERSAILLES PARIS, FRANCE 29TH SEPTEMBER - 4TH OCTOBER 2019 Tuesday, 1st October 9:30 - 18:00 Wednesday 2nd October 9:30 - 17:30 Thursday 3rd October 9:30 - 16:30

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EuMIC08-1

Ka to W Band GaN/Si Power Amplifiers

Rémy LEBLANC^{#1}, Ahmed GASMI^{#1}, Majid El KAAMOUCHI^{#1}, Joël MORON^{#1}, Ousmane SOW^{#1}, Peter FRIJLINK^{#1}, François LECOURT^{#1}, Charles EDOUA KACOU^{#1}, Julien POULAIN^{#1}, Florent GAMAND^{#2}, Oscar LEVEILLE^{#2}

#1OMMIC, France #2MC2-Technologies, France r.leblanc@ommic.com





















1 St 6 Inch GaN line in Europe

- Created in 2000, III-V activities started in 1970
- Former Philips Semiconductor division
- Over 49 years of experience in III-V semiconductors, including GaAs and InP
- Unique GaN Process best suited for upcoming 5G
- Only foundry in Europe offering complete service including Epitaxial Growth, Process Development, MMIC Design & Fabrication, Test & Product Qualification















20 m





20 km



A ENTRANCE A





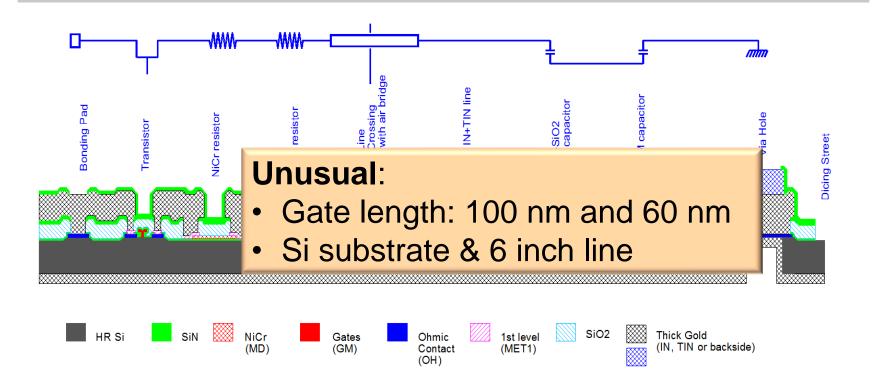






OMMIC GaN/Si MMIC process

Full MMIC Process for mm-wave designs Via holes, air-bridges, metal resistors, MIM capacitors















Si substrate!! Why not SiC??

- Cons...
 - Higher Rth ?
 - Yes, but in fact only x2, compatible with the power levels required at mm wave and with the 12V quiescent voltage of OMMIC GaN
 - Higher microwave losses ?
 - We use HR Si with good buffer, only 0.3dB/mm@30 GHz
- Pros...
 - Lower cost, larger diameters, thus compatible with 5G volumes
 - Lower risk of import/export restrictions
 - Compatible with heterogeneous integration with SiGe/CMOS





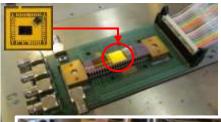








OMMIC GaN/Si process reliability



Reliability evaluation completed in the frame of a Thales CS / DGA contract



- Storage 3 temperatures
- DC life test at 6 channel temperatures and 2 VDDs (12V & 15V)
- HTRB tests at 2 reverse biasing points (24 & 30V)
- RF step stress up to 7dBc by steps of 168h
- RF life test at 3dBc
- MTTF 3.10⁷ hours at 200°C channel temperature

Full ESCC-compatible Space Evaluation running in the frame of H2020 MiGaNSOS project, with UTV, TAS-I, VTT, OMMIC

The MIGANSOS project has received funding from the European Union's Horizon 2020 research and innovation programme under grant agreement No 779305















OMMIC GaN/Si process from statistics

Electrical Characteristic	Gate 100 nm	Gate 60 nm
Frequency Cutoff	105 GHz	130 GHz
MSG at 30 GHz (2x25µm device)	13 dB	13.5 dB
RF power density	3.3 W/mm	3.3 W/mm
NF min at 40 GHz	1.5 dB	1.1 dB
Extrinsic Transconductance	800 mS/mm	950 mS/mm
Extrinsic Drain Source resistance (Ron)	0.6 Ω.mm	0.6 Ω.mm
Gate Drain voltage for 300μA/mm	>50 V	>50 V
Maximum Drain Current at Vds=3V	1.3 A/mm	1.6 A/mm
Recommended Quiescent VDD	12 V	12 V











Tips to design PAs with OMMIC GaN/Si

- Gain is high!
 - 800 μm devices can be used even at 40 GHz
 - Use stabilization networks in X or Ku band
- Usual Quiescent voltage is 12 V
 - Breakdown is above 50 V
- Usual biasing is AB class (Imax/8, approx 200 mA/mm)
- Loadlines of individual transistors should be set by design to maintain dissipated power (Pdiss) below 3.5 W/mm (2.5W/mm for space) in large signal (CW)
 - Pdiss = PDC + PRFin PRFout = PDC \times (1 PAE)





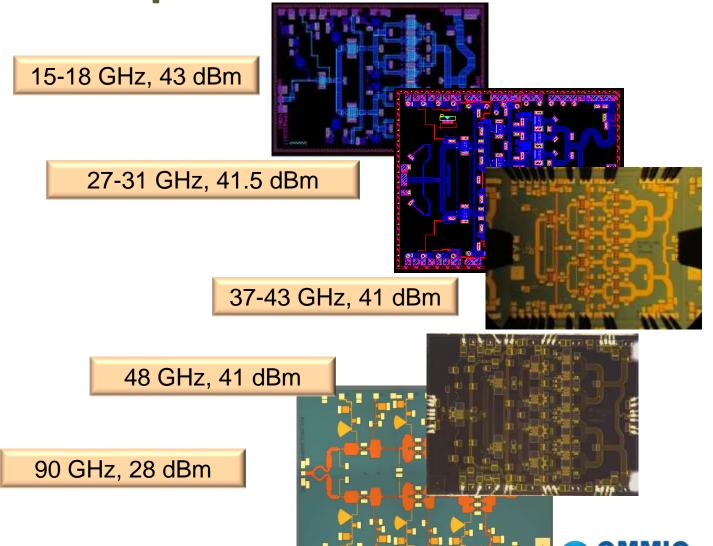








A few examples of PAs





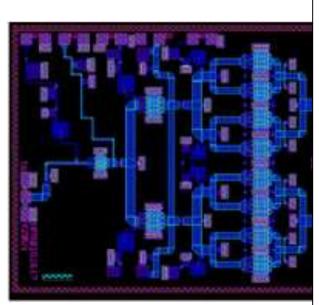


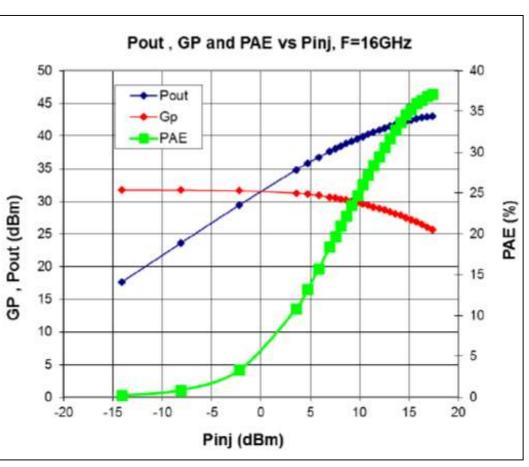






15-18 GHz, 20 W, 37% PAE





On wafer pulsed test





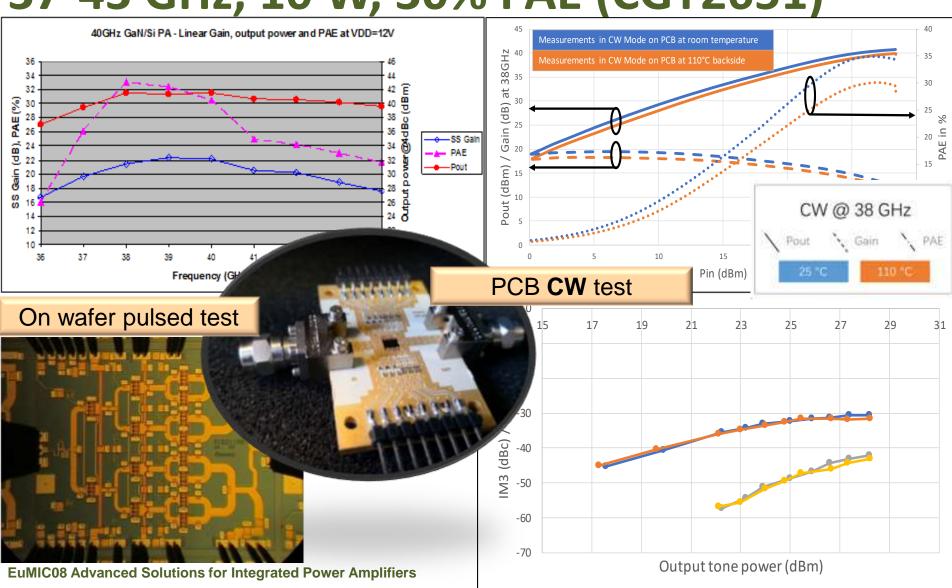








37-43 GHz, 10 W, 30% PAE (CGY2651)





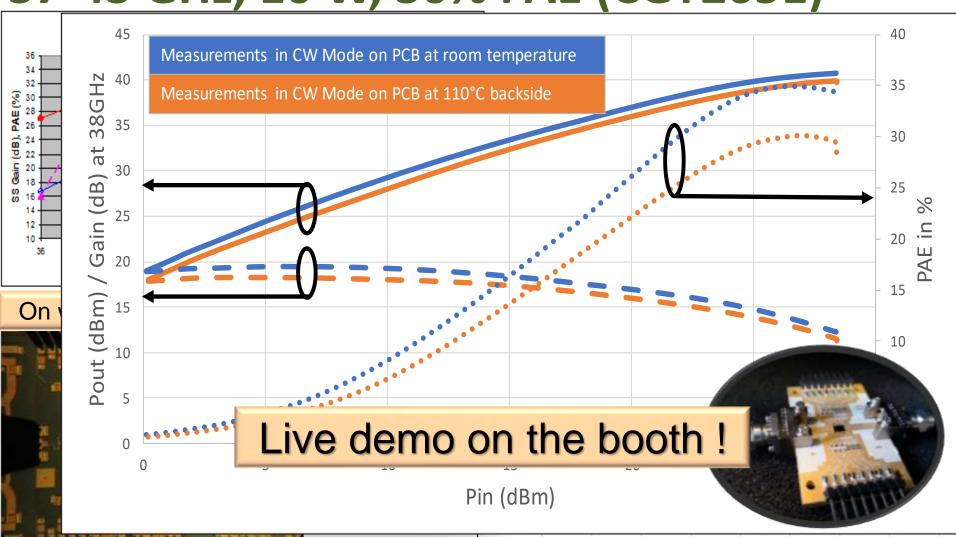








37-43 GHz, 10 W, 30% PAE (CGY2651)











CGY2651 CW live demo at EuMW 2019

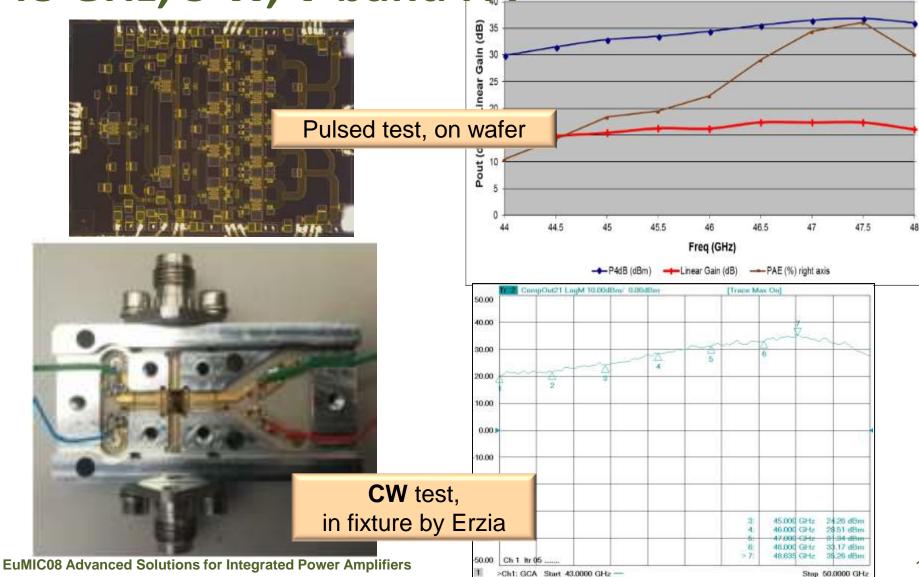






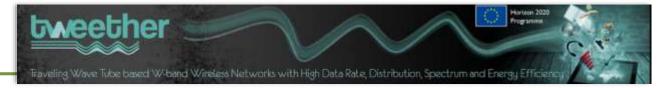


48 GHz, 5 W, V band PA

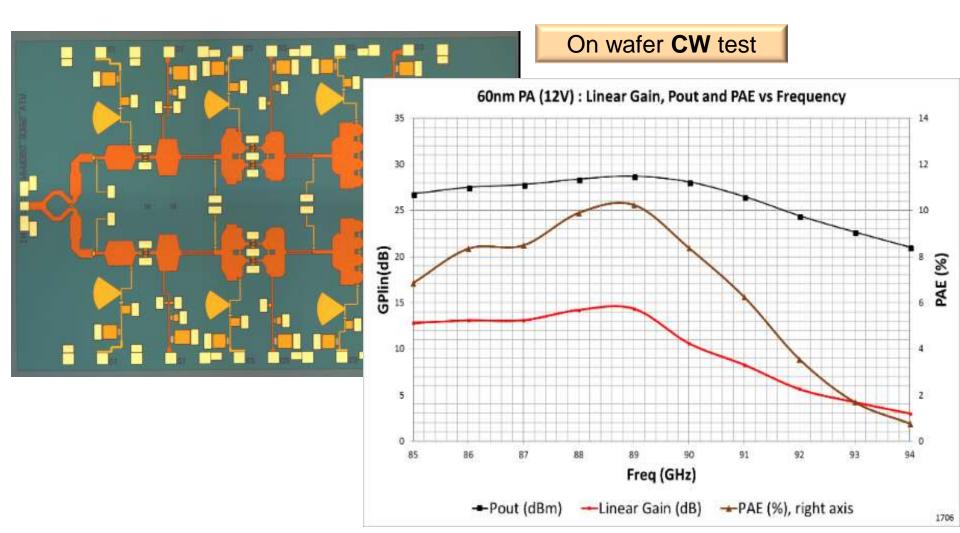








27 dBm 90 GHz PA D006GH (60 nm)





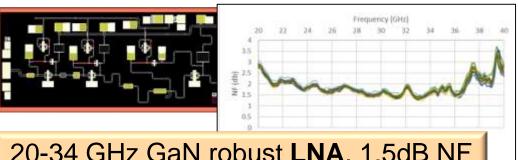








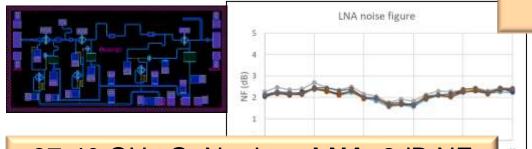
What else? OMMIC GaN not only for PAs!



T/R chip receive mode (Switch + LNA)

20-34 GHz GaN robust LNA, 1.5dB NF

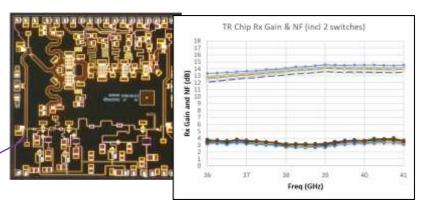
30 GHz TR Chip (LNA+PA+Switch) 36 dBm, 2.7 dB NF incl switch



37-40 GHz GaN robust LNA, 2dB NF

The SERENA project has received funding from the European Union's Horizon 2020 research and innovation programme under grant agreement No 779305.





39 GHz TR Chip (LNA+PA+2 Switches) 35 dBm, 3.3 dB NF incl switches

EuMIC08 Advanced Solutions for Integrated Power Amplifiers











Conclusion

 100 nm and 60 nm GaN/Si microwave process can be used as conventional PHEMT « but with more power » for power amplifers from Ku to W band

- With careful design strategy and with the margin given by short gate length, Si allows state of the art performances and excellent reliability with lower cost and less regulation constraints than SiC, opening the possibility of realistic volume production of 5G MMICs at 28GHz, 39GHz and E-band for BackHaul
- The same process presents excellent noise allowing robust LNA products and multifunction SCFE chips











Thank you!